

**Form PTO-1449 (modified)**

List of Patents and Publications  
For Applicant's Information  
Disclosure Statement  
(Use several sheets if necessary)

ATTY. DOCKET NO: 5298-05500

SERIAL NO: 09/476,669



APPLICANT: Lau

FILING DATE: December 30, 1999

GROUP: 2811

**U.S. PATENT DOCUMENTS**

EXAM. INITIALS	REF. DES	DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE
HC	AA	4,970,176	11/13/90	Tracy et al.			
HC	AB	5,108,570	4/28/92	Wang			
HC	AC	5,108,951	4/28/92	Chen et al.			
HC	AD	5,270,255	12/14/93	Wong			
HC	AE	5,288,665	2/22/94	Nulman			
HC	AF	5,358,616	10/25/94	Ward			
HC	AG	5,371,042	12/6/94	Ong			
HC	AH	5,378,660	1/3/95	Ngan et al.			
HC	AI	5,443,995	8/22/95	Nulman			
HC	AJ	5,600,182	2/4/97	Schinella et al.			
HC	AK	5,665,659	9/9/97	Lee et al.			
HC	AL	5,693,564	12/2/97	Yu			
HC	AM	5,731,245	3/24/98	Joshi et al.			

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**OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)**

HC	AN	Xu et al., "Plar Multilevel Metallization Technologies for ULSI Devices," SPIE Vol. 2335, 1994, pp. 70-79.
HC	AO	Xu et al., "A1 planarization processes for multilayer metallization of quarter micrometer devices," Thin Solid Films, Vol. 253, 1994, pp. 367-371.
HC	AP	Singer, "The Interconnect Challenge: Filling Small, High Aspect Ratio Contact Holes," Semiconductor International, August 1994, 5 pages.
HC	AQ	Robinson, "A1 hits sub-0.25 micron vias," pp. 37 and 42, Electronic Engineering Times, Issue 939, February 1997.
HC	AR	Metal Deposition Products, Applied Materials-Products and Services, 5 pages, printed November 1999, © 1999 Applied Materials, Inc.
HC	AS	"Ionized Physical Vapor Deposition," printed December 1999, www.ece.neu.edu/edsnu/hopwood, 8 pages.

EXAMINER:

*H. Cantelero*

DATE CONSIDERED:

*2/28/01*

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to the patent owner.

Information Disclosure Statement--PTO 1449 (modified)

**Form PTO-1449** (modified)

ATTY. DKT. NO. 5298-03500

SERIAL NO. 09/476,669

List of Patents and Publications

For Applicant's Information

APPLICANT: Lau

GROUP: 1753

Disclosure Statement

FILING DATE: December 30, 1999

17 (Use several sheets if necessary)

**U.S. PATENT DOCUMENTS**

EXAM. INITIALS	REF. DES.	DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE
<i>JK</i>	B1	5,658,828	8/1997	Lin et al.			
<i>JK</i>	B2	5,985,759	11/1999	Kim et al.			
<i>JK</i>	B3	6,080,665	6/2000	Chen et al.			
<i>JK</i>	B4	6,093,654	7/2000	Koyama			

**FOREIGN PATENT DOCUMENTS**

EXAM. INITIALS	REF. DES.	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUB CLASS	TRANSLATION YES/NO

**OTHER ART** (Including Author, Title, Date, Pertinent Pages, Etc.)


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